

	Hits	Search Text
1	26	etch\$3 same (low adj k "low-k" low near dielectric BCB SiLK FLARE parylene polysiloxane) same ((CF4 "CF.sub.4") and (N2 "N.sub.2"))
2	104701	sio.sub??
3	11	etch\$3 same (low adj k "low-k" low near dielectric BCB SiLK FLARE parylene polysiloxane) same ((CF4 "CF.sub.4") and (N2 "N.sub.2")) same (SiO2 "Si0.sub.2" ?sio.sub?? silicon adj
4	15	(etch\$3 same (low adj k "low-k" low near dielectric BCB SiLK FLARE parylene polysiloxane) same ((CF4 "CF.sub.4") and (N2 "N.sub.2")) not (etch\$3 same (low adj k "low-k" low near dielectric BCB SiLK FLARE parylene polysiloxane) same ((CF4 "CF.sub.4") and (N2 "N.sub.2")) same (SiO2 "Si0.sub.2" ?sio.sub?? silicon adj
5	2	etch\$3 same (low adj k "low-k" low near dielectric BCB SiLK FLARE parylene polysiloxane) same ((C4F8 "C.sub.4 F.sub.8") and (N2 "N.sub.2")) same (Si3N4 SiN "Si.sub.3 N.sub.4" Si?sub.3 adj N?sub.4 sio.sub?? silicon adj
6	10	(US-6325861-\$ or US-6323121-\$ or US-6399424-\$ or US-6284149-\$ or US-4946549-\$ or US-6243146-\$ or US-6265320-\$).did. or (US-20010010567-\$ or US-20010026952-\$).did. or (EP-790645-\$).did.
7	10	((US-6325861-\$ or US-6323121-\$ or US-6399424-\$ or US-6284149-\$ or US-4946549-\$ or US-6243146-\$ or US-6265320-\$).did. or (US-20010010567-\$ or US-20010026952-\$).did. or (EP-790645-\$).did.) and (CF4 "CF.sub.4")

	DBs
1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
6	USPAT; US-PGPUB; DERWENT
7	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB